

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of: Jung Wook LIM, et al.
Serial No.: New Application Group Art Unit: Not Yet Assigned
Filed: August 22, 2003 Examiner: Not Yet Assigned
Title: METHOD OF FORMING A THIN FILM IN A SEMICONDUCTOR DEVICE

INFORMATION DISCLOSURE STATEMENT

Honorable Commissioner for Patents
PO Box 1450,
Alexandria, VA 22313

August 22, 2003


Sir:

As a means of complying with the duty of disclosure under 37 CFR §1.56, and in accordance with 37 CFR §§1.97 and 1.98, Applicant(s), through the undersigned attorney, submits this Information Disclosure Statement. The patents, publications or other information submitted herewith are listed on the attached Form PTO-1449 and copies are attached.

In accordance with 37 CFR §1.97(b)(1) or (2), this Information Disclosure Statement is being filed either within three months of the filing date of the above-identified application, or within three months of the date of entry into the national stage of the above-identified application as set forth in 37 CFR §1.491. Accordingly, no fee is required.

Respectfully submitted,

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LIST OF PATENTS AND PUBLICATIONS FOR APPLICANT'S INFORMATION DISCLOSURE STATEMENT

ATTY. DOCKET NO.: P69084US0 GROUP ART UNIT: Not Yet Assigned
 SERIAL NO.: Not Yet Assigned FILING DATE: August 22, 2003
 APPLICANT(S): Jung Wook LIM, et al. TODAY'S DATE: August 22, 2003

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	INT'L CLASS	SUB- CLASS	FILING DATE (If Appropriate)
AA	6,416,822	7/09/02	Chiang, et al.	B05D	3/00	3/19/01
AB	6,468,924	10/22/02	Lee, et al.	H01L	21/31	5/31/01

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB- CLASS	TRANSLATION (YES) (NO)
AC	2002-46431	06/21/02	KOREA (ROK)	H01L	29/108	X
AD						
AE						

OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)

AF Jin-Seong Park, et al.; "Plasma-Enhanced Atomic Layer Deposition of Ta-N Thin Films"; Journal of The Electrochemical Society, 149 (1) C28-C32 (2002).

AG Hyun-Jung Song, et al.; "Increment of the Dielectric Constant of Ta₂O₅ Thin Films by Retarding Interface Oxide Growth on Si Substrates"; Electrochemical and Solid-State Letters, 4(7) F13-F14 (2001).

EXAMINER

DATE CONSIDERED

* EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant(s).